



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Patricia B. Smith et al.

Docket No.: TI-25250

Filed: 11-25-98

Art Unit: 2823

Serial No: 09/199,829

Examiner: Eaton, K.

For: HYDROGEN PLASMA PHOTORESIST STRIP AND POLYMERIC RESIDUE
CLEANUP PROCESS FOR OXYGEN-SENSITIVE MATERIALS

EXTENSION OF TIME

Assistant Commissioner for
Patents
Washington, DC 20231

MAILING CERTIFICATE UNDER 37 C.F.R. §1.8(a)
I hereby certify that the above correspondence is being deposited with the
U.S. Postal Service as First Class Mail in an envelope addressed to:
Assistant Commissioner for Patents, Washington, D.C. 20231 on:
September 28, 2000.

Cecelia Grant
Cecelia Grant

Dear Sir:

Pursuant to 37 CFR 1.136(a), Applicants respectfully petition the Commissioner for an extension of the
shortened statutory period for response in the above-identified Application.

The fee for this extension is indicated below:

___ One Month (\$110)
x Two Months (\$380)
___ Three Months (\$870)
___ Four Months (\$1,360)

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Please charge any required time extension or other fee that may be required incident to the filing of the
accompanying paper(s) to Deposit Account No. 20-0668, and grant any further necessary extension of time that may be
required. Charge any and all fees to Deposit Account No. 20-0668. This form is submitted in triplicate.

10/11/2000 ZLT:TES 00000042 200668 09199829
01 FC:116 380.00 CH

Respectfully submitted,

Texas Instruments Incorporated
P.O. Box 655474, M/S 3999
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